

**N91-14384****LWIR HgCdTe - INNOVATIVE DETECTORS  
IN AN INCUMBENT TECHNOLOGY****W. E. TENNANT****Rockwell International  
Science Center  
Thousand Oaks, California****ABSTRACT**

HgCdTe is the current material of choice for high performance imagers operating at relatively high temperatures. Its lack of technological maturity compared with silicon and wide-band gap III-V compounds is more than offset by its outstanding IR sensitivity and by the relatively benign effect of its materials defects. This latter property has allowed non-equilibrium growth techniques (MOCVD and MBE) to produce device quality LWIR HgCdTe even on common substrates like GaAs and GaAs/Si. Detector performance in these exotic materials structures is comparable in many ways with devices in equilibrium-grown material. Lifetimes are similar. RoA values at 77K as high as several hundred have been seen in HgCdTe/GaAs/Si with 9.5  $\mu\text{m}$  cut-off wavelength. HgCdTe/GaAs layers with  $\sim 15 \mu\text{m}$  cut-off wavelengths have given average 77K RoAs of  $>2$ . Hybrid focal plane arrays have been evaluated with excellent operability.

# LWIR HgCdTe - INNOVATIVE DETECTORS IN AN INCUMBENT TECHNOLOGY

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## OVERVIEW

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- 0 PACE BACKGROUND AND MATERIALS**
- 0 TEST DIODE PERFORMANCE AND TECHNOLOGY LIMITS**
- 0 PRELIMINARY LWIR ARRAY DATA**
- 0 DIRECTIONS AND CONCLUSIONS**

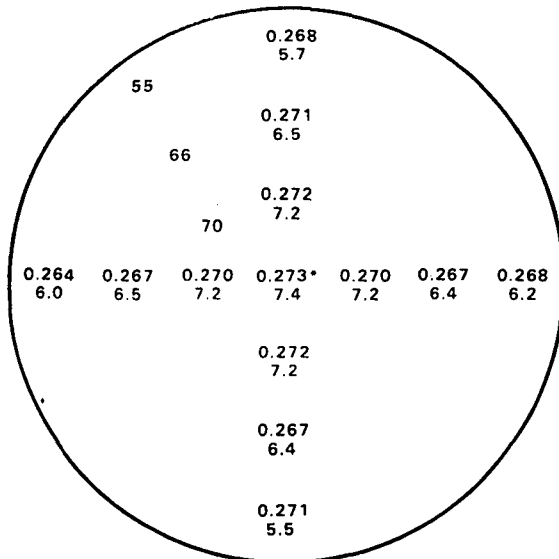


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# DEFINITIONS

- **CONVENTIONAL TECHNOLOGY**
  - MCT GROWN BY LIQUID PHASE EPITAXY ON CdTe OR SIMILAR COMPOUND
- **PACE (PRODUCIBLE ALTERNATIVE TO CdTe FOR EPITAXY)**
  - ROCKWELL APPROACH TO OVERCOME MCT PRODUCIBILITY ISSUES
  - **PACE-1:** MCT GROWN BY LIQUID PHASE EPITAXY ON VAPOR PHASE EPITAXIAL CdTe/SAPPHIRE -- SUITABLE FOR SWIR (1-3 MICRONS) AND MWIR (3-5+) MICRONS
  - **PACE-2:** MCT GROWN BY VAPOR PHASE EPITAXY ON GaAs (OR EVENTUALLY Si) -- SUITABLE FOR ALL IR WAVELENGTHS

## PACE-2 HAS BETTER COMPOSITIONAL UNIFORMITY THAN LPE



3" DIA GaAs WAFER

$$\max \frac{\Delta x}{\bar{x}} = 3.3\%, \max \frac{\Delta \bar{d}}{\bar{d}} = 29\% \text{ OVER } 3'' \text{ DIA}$$

$$\max \frac{\Delta x}{\bar{x}} = 2.2\%, \max \frac{\Delta \bar{d}}{\bar{d}} = 17\% \text{ OVER } 2'' \text{ DIA}$$

**LEGEND**

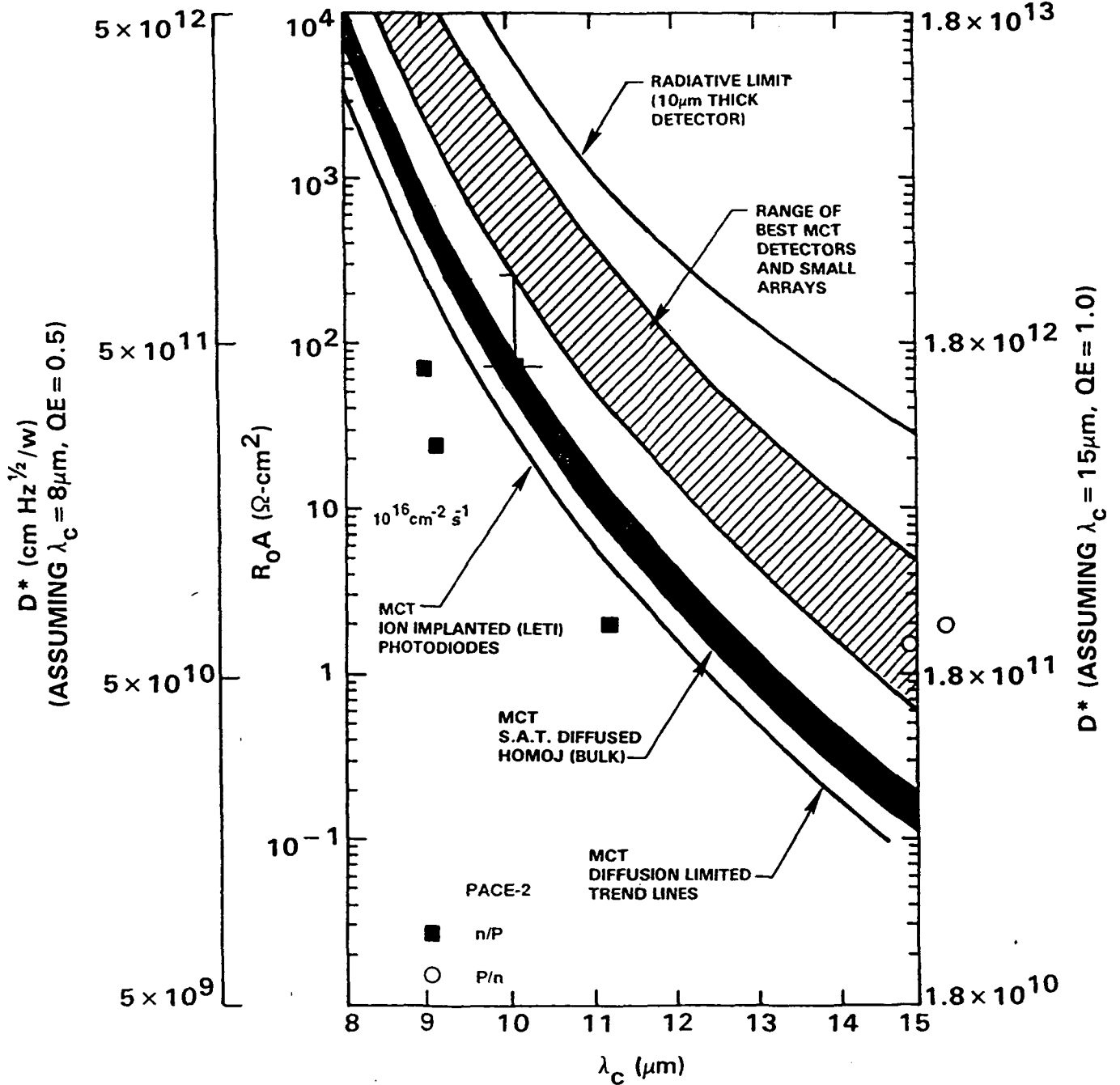
- \* - COMPOSITION, X VALUE
- THICKNESS,  $\mu\text{m}$
- CRYSTALLINITY, ARC-SEC



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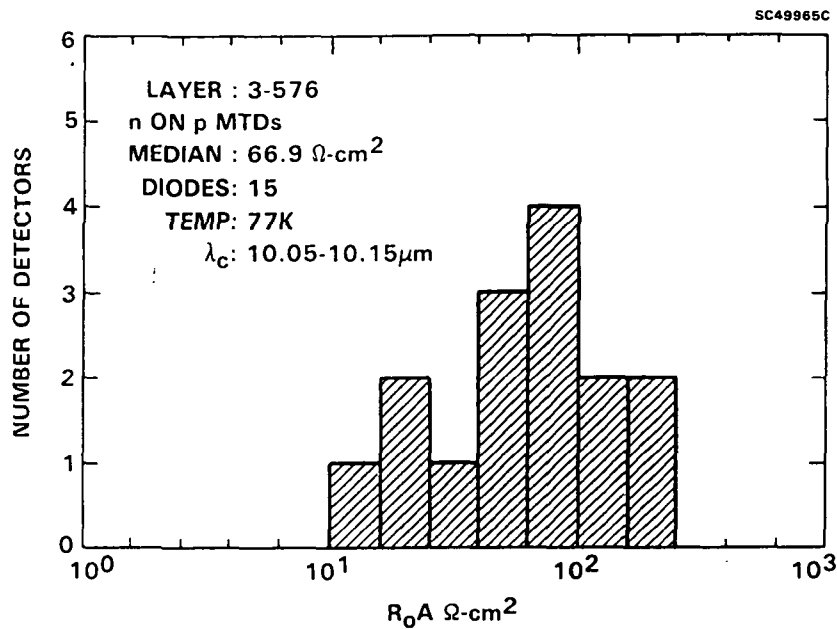
# LWIR TACTICAL MCT DETECTOR PERFORMANCE

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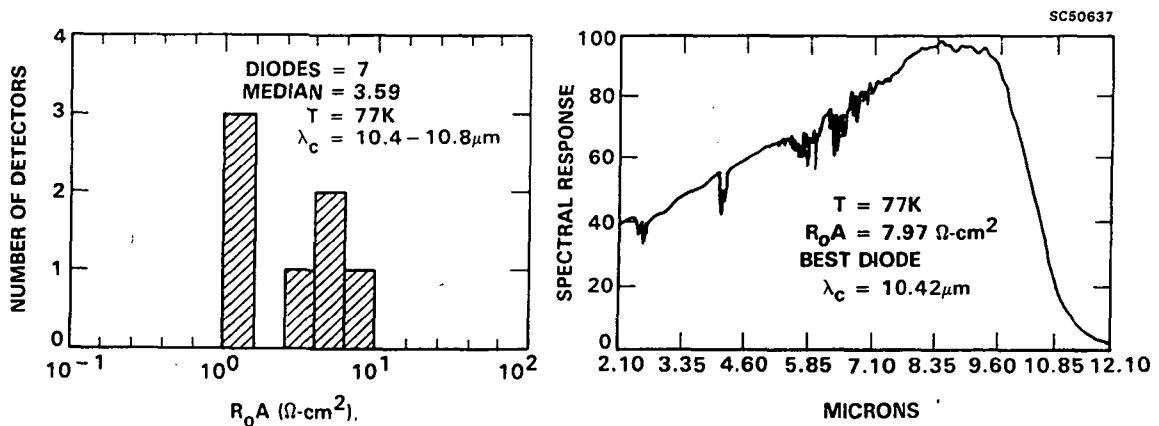


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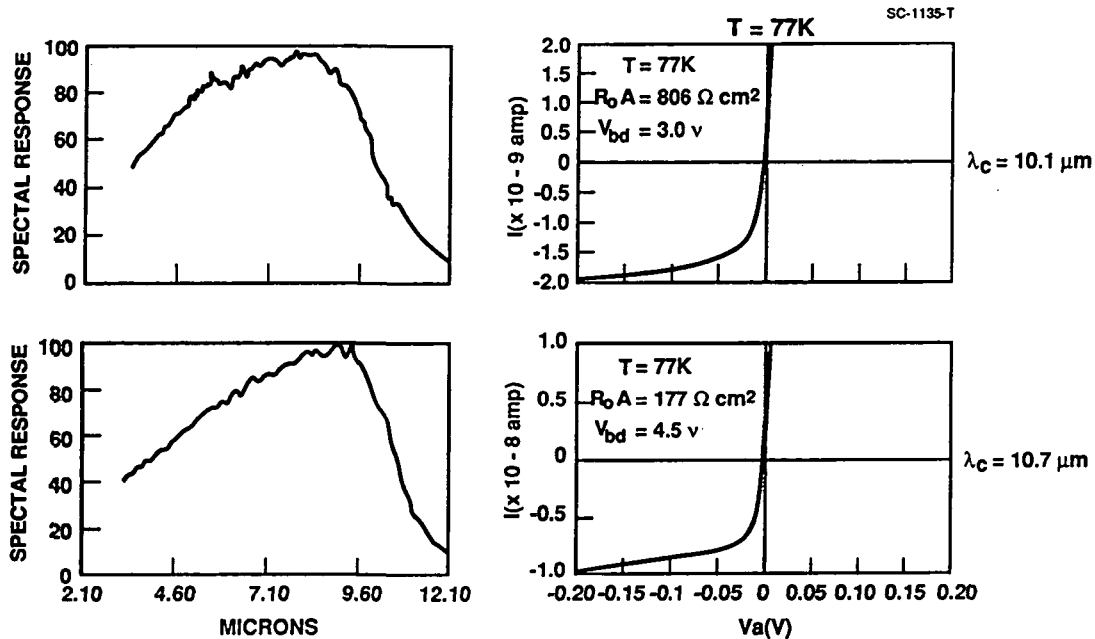
# $n^+ / p$ TEST DIODES IN HgCdTe/GaAs (PACE-2)



## MTD DATA FOR 3-623 BASELINE LAYER n ON p DEVICES, ION IMPLANTED



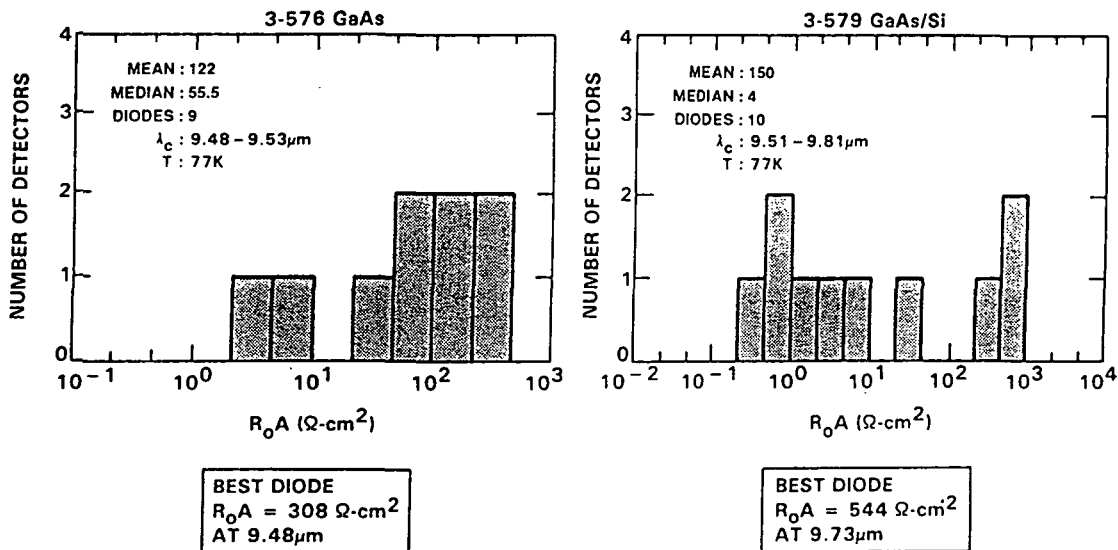
# LWIR HgCdTe/Pace-2 p/n Devices Show Higher Performance Than LPE Devices



- ARSENIC IMPLANTATION
- OMVPE HgCdTe ON GaAs

## RECENT p ON n MTD PERFORMANCE CONFIRM EARLIER RESULTS

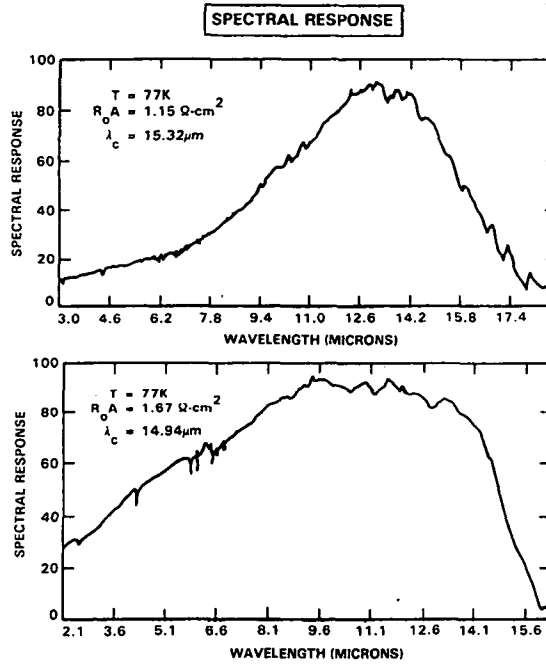
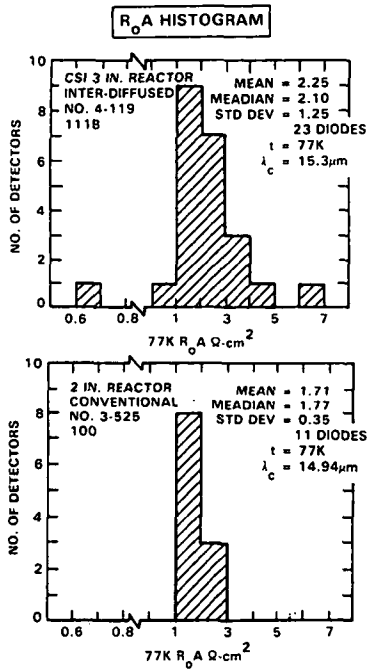
### ARSENIC IMPLANT/DIFFUSION IN DOUBLE LAYER HETEROSTRUCTURE



- n ON p DIODES HAVE BETTER UNIFORMITY

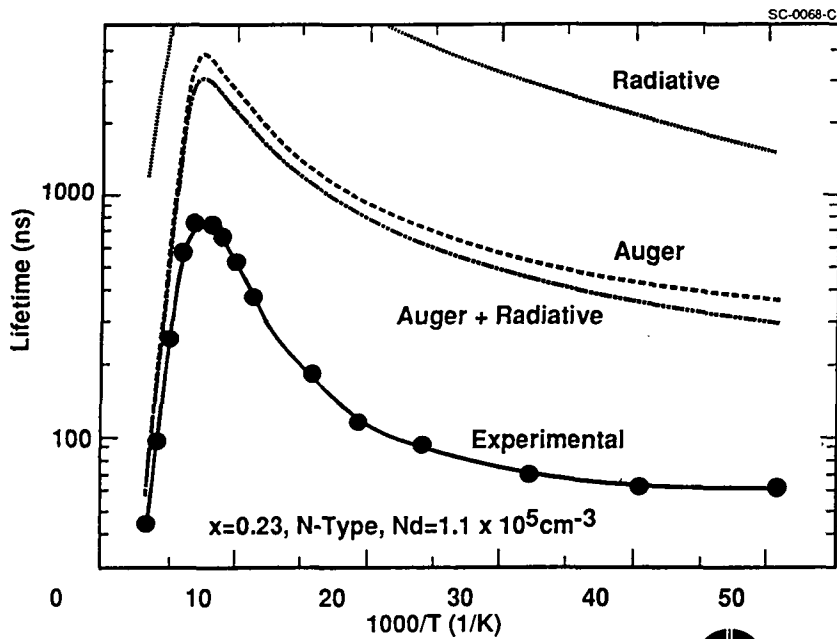
# EXCELLENT DIODE PERFORMANCE IN VLWIR MOCVD MCT/GaAs p ON n DIODES

SC48214



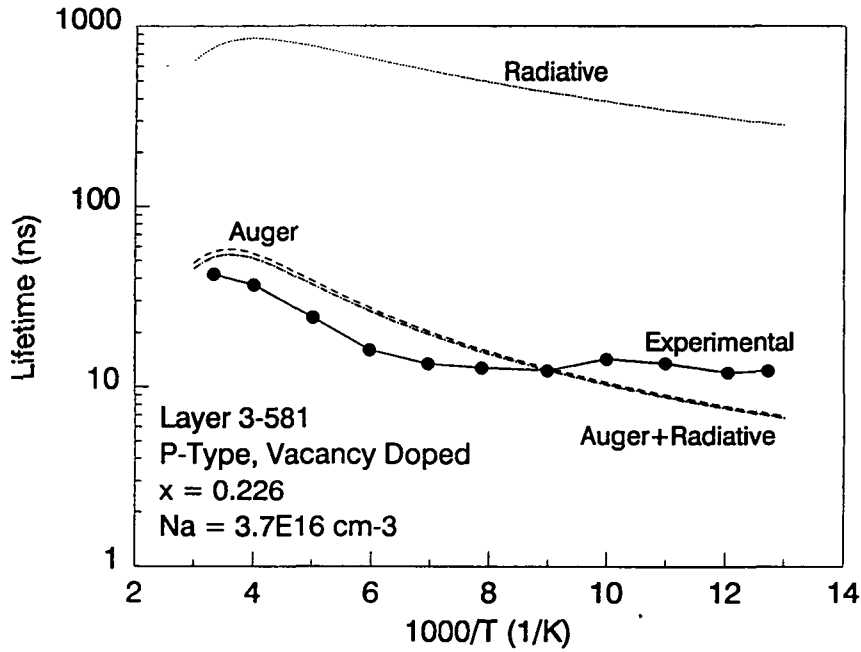
## Minority Carrier Lifetime

4-334, N-Type, Undoped,  $x=0.235$ ,  $N_d=1.1 \times 10^{15}\text{cm}^{-3}$

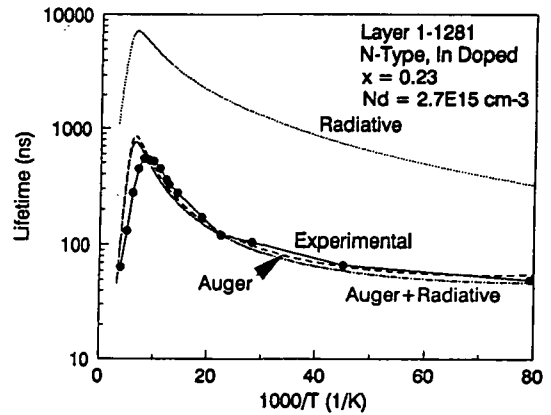
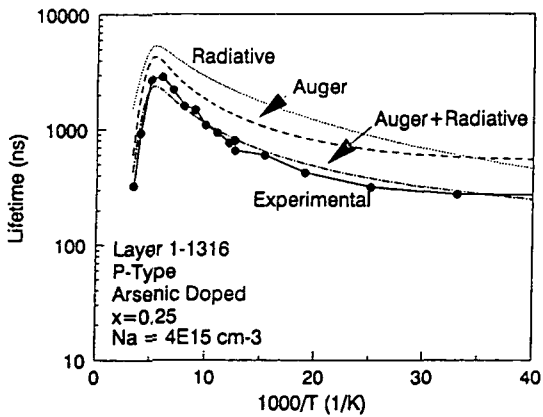


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## LIFETIMES IN SOME VACANCY DOPED PACE-2 APPROXIMATE THEORY

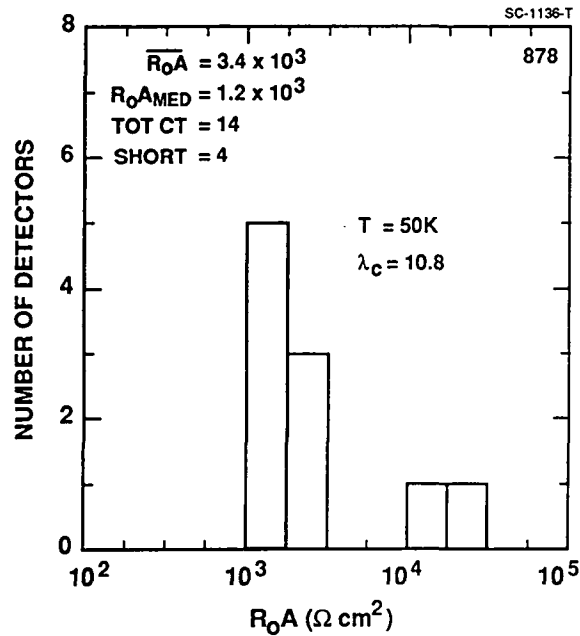


## BEST IMPURITY DOPED PACE-2 SAMPLES SHOW THEORETICAL LIFETIMES

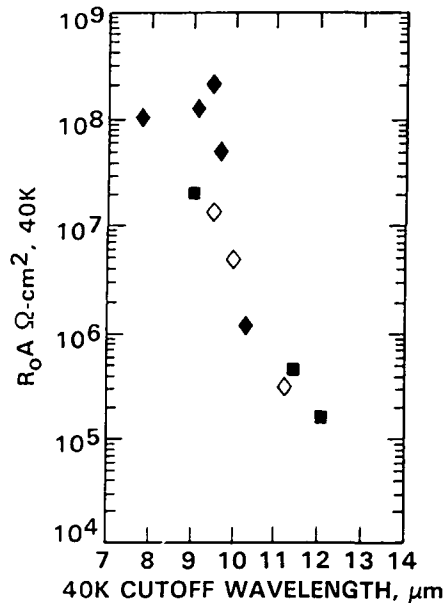




# Performance of an LWIR MCT/GaAs Array at 50K



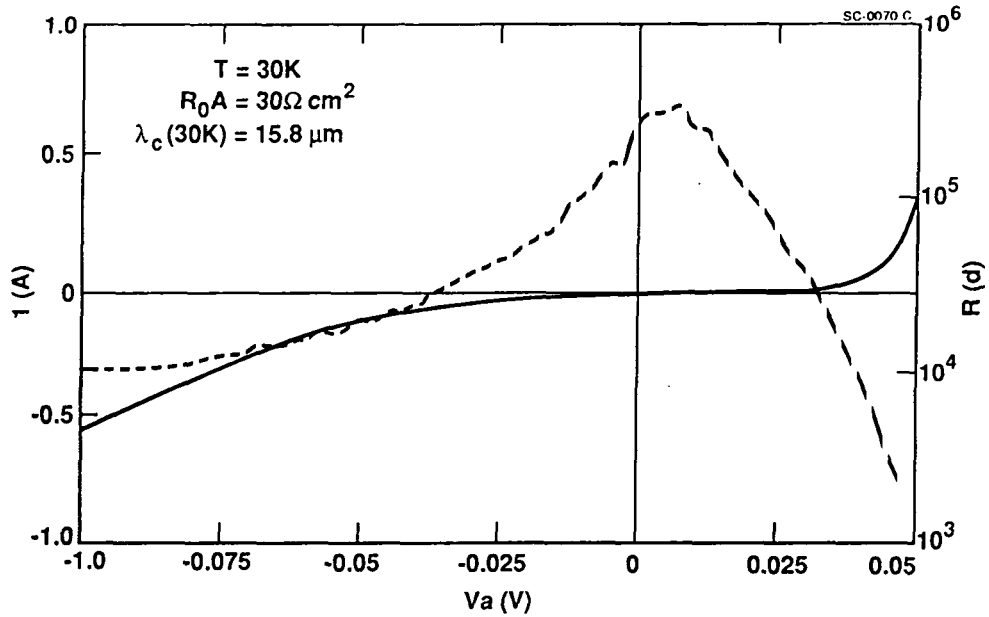
## LWIR MOCVD HgCdTe/GaAs DIODES BEST PERFORMANCE IS AT TOP LPE LEVELS FOR 77 AND 40K



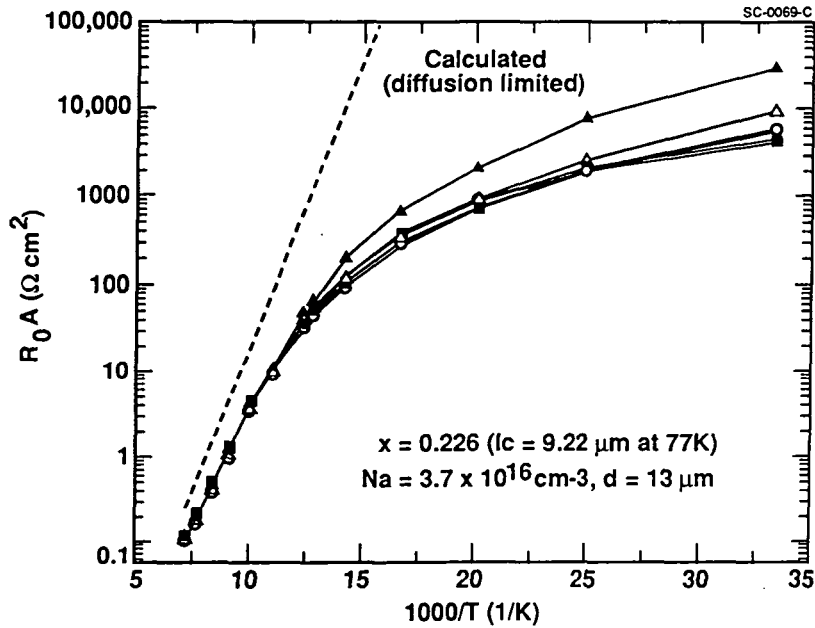
**LEGEND**  
 LPE MCT/CdTe     $\blacklozenge$      $\diamond$   
 MOCVD MCT/GaAs     $\blacksquare$


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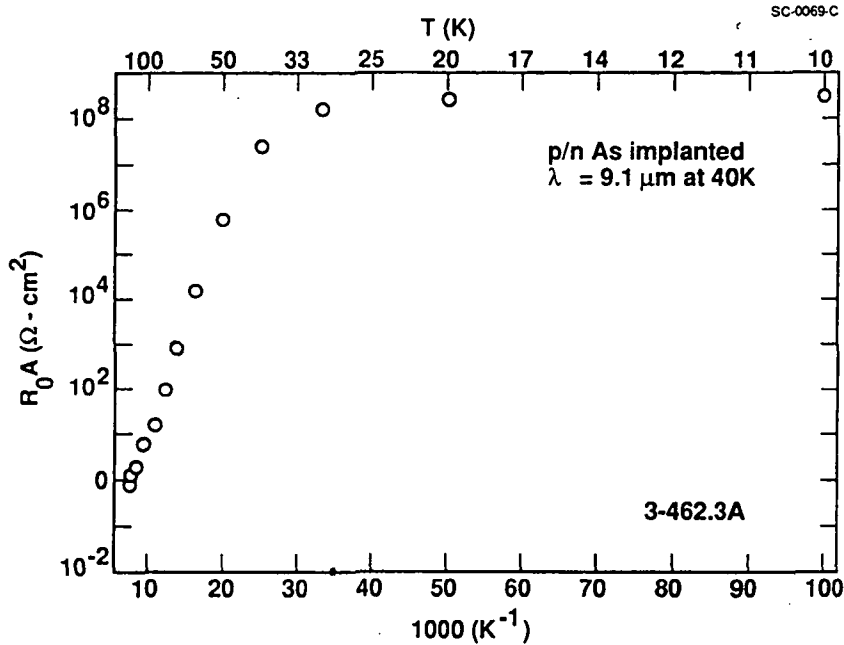
# VLWIR I-V Characteristics for MOCVD Grown MCT/GaAs Detector



## $R_0A$ vs $1/T$ Layer 3-581, L-134, Planar Ion Implanted

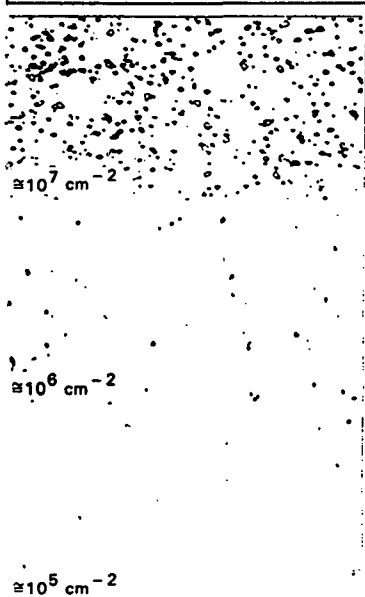


# Temperature Dependence of the $R_0A$ Product of a P/N Diode Fabricated from PACE-2 Material



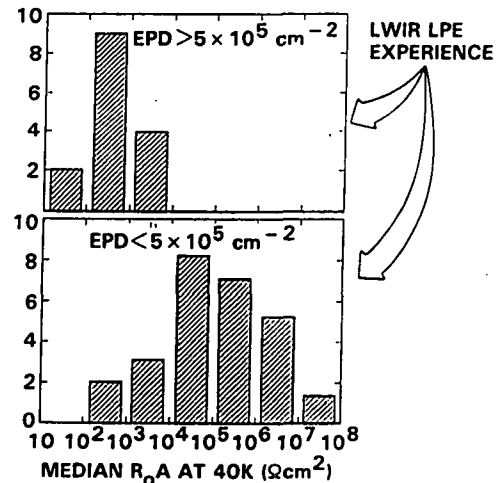
## STRATEGIC APPLICATIONS REQUIRE CONTROL OF DISLOCATION DENSITY

ETCH PIT DENSITY MCT/GaAs



### LOW TEMPERATURE OPERATION IS MOST DEMANDING APPLICATION

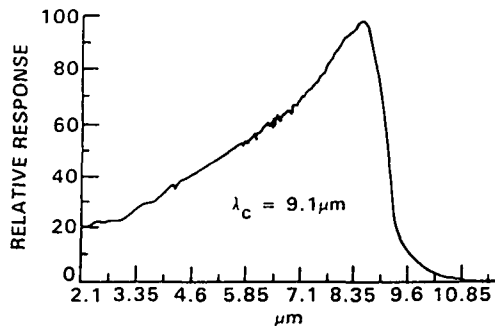
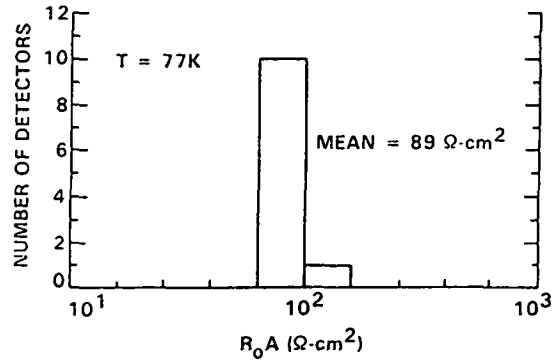
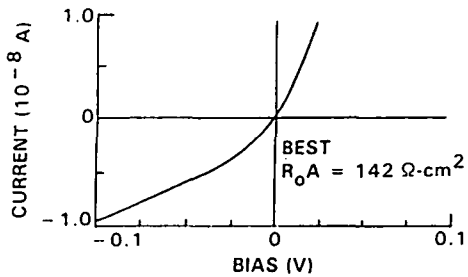
SC49582



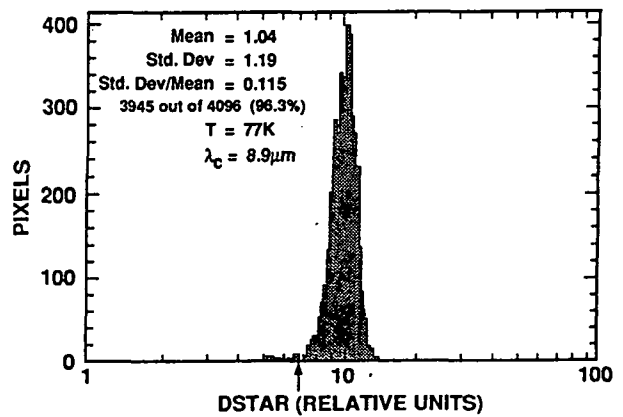
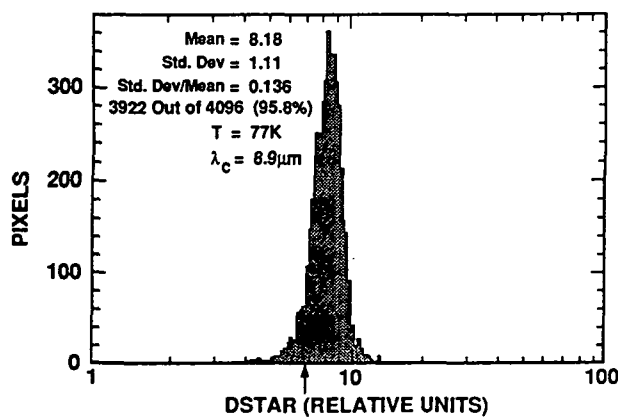
$\lambda_c \geq 9.1\text{-}10.3 \mu\text{m}$  AT 40K FOR 38 LAYERS

# SAMPLE DIODES FROM PACE II 128 x 128 WAFER (ROCKWELL IR&D)

FULL PLANAR PROCESS: n/p, B-IMPLANTED, ZnS/SiO<sub>2</sub> PASSIVATED



## Pace-2 Shows D\* Uniformity and Operability of LWIR Hybrid



# CONCLUSIONS

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- MCT HAS DEMONSTRATED THE HIGHEST PERFORMANCE OF ANY INTRINSIC AT ALL IR WAVELENGTHS
- NOVEL, ALTERNATIVE-SUBSTRATE, VPE APPROACHES CAN MEET PROGRAM GOALS WHILE ENHANCING PRODUCIBILITY AND MAKING POSSIBLE ADVANCED ARCHITECTURES
- THE PRESENT LIMITATIONS OF THE TECHNOLOGY ARE NOT FUNDAMENTAL BUT DUE TO IMMATURITY
- WE EXPECT LWIR/PACE-2 (GaAs)OR 3 (Si) TO FOLLOW A SIMILAR PATH TO PRODUCIBILITY AS THAT OF MWIR PACE-1 WHICH HAS RESULTED IN THE LARGEST (256X256) INSTRINSIC IR FPA TO DATE



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